

	Hits	Search Text	DBs
40	1	((photoresist or resist) same (non\$4chemical\$5amplif\$6) same (resin\$3) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) and (photo\$5active or photoactivat\$4 or (light near9 activat\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
41	1	((photoresist or resist) same (non\$4chemical\$5amplif\$6) same (resin\$3) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
42	15	((photoresist or resist) same (resin\$3) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) and (photo\$5active or photoactivat\$4 or (light near9 activat\$4)) and (non\$4 near9 chemical\$2 near9 amplif\$6)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
43	34	((photoresist or resist) same develop\$4 same (expos\$4 or illuminat\$3 or irradiat\$3)) and ((photo\$5active or photoactivat\$4 or (light near9 activat\$4)) same acid) and (non\$4 near9 chemical\$2 near9 amplif\$6)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB